



DPS2009

(The 31st International Symposium on Dry Process)

Call for Papers

September 24 (Thu) - 25 (Fri) 2009
Busan Exhibition & Convention Center,
Busan, Korea

<http://www.bexco.co.kr/english/main/main.jsp>

Organizing Chair

T. Oiwa (Toshiba Corp.)

Executive Chair

M. Shiratani (Kyushu Univ.)

Program Chair

T. Tatsumi (Sony Corp.)

Publication Chair

K. Sasaki (Nagoya Univ.)

The 31st International Symposium on Dry Process will be held at Busan Exhibition & Convention Center, Busan, Korea on September 24-25, 2009. Dry Processes are the state of the art technologies leading the way through ultra-high performance in microelectronic devices. The DPS has provided for 30 years a valuable forum of discussion on science and technology of new developments in this field. This symposium be held in Busan, Korea in conjunction with Korean organizations PSE2009 (<http://www.pse2009.org/>) and ICMAP.

SUBMISSION OF ABSTRACT

The DPS Organizing Committee invites you to the conference and welcomes the submission of your papers. Authors are requested to submit via the web site. <http://www.dps2009.org/>
Deadline: May 31, 2009.

REGISTRATION FEE

Category	DPS Regular	DPS Student	DPS +PSE/ICMAP Regular	DPS +PSE/ICMAP Student
Before July 31	300 USD	150 USD	550 USD	250 USD
Late	350 USD	200 USD	600 USD	300 USD
Banquet	Not included	Not included	Not included	Not included
Registration site	http://www.dps2009.org/		http://www.pse2009.org/	

Plenary speakers

M. Koyanagi (Tohoku Univ.)

C. J. Kang (Samsung)

Invited speakers

N. Miyakawa

(Honda Research Institute)

J. Matsuo (Kyoto Univ.)

L. Chen (Tokyo Electron)

S. Rauf (Applied Materials)

Attendees for DPS only: Payment by credit card is accepted only by Japanese yen.
Please refer to the DPS website for detailed information.

TOPICS

Plasma & Surface Reactions

Conductor & Si Etching

Dielectric Etching

Plasma-induced Damage

Plasma Diagnostics

Modeling and Simulation

Plasma Equipment

Monitoring Systems

CVD/PVD/ALD

Plasma processes for

3D Devices,

FPD, LED, LASER,

Organic Devices,

Bio-Application,

Medicine, MEMS,

Nanotechnologies, and

Environmental Technology

Processes using Atmospheric

and Liquid Plasmas

New Dry Process Concepts

Wet Process & Reactions

PUBLICATION

The authors of the superior papers will be recommended by the committee to submit the papers for the publication in the **JJAP special issue** of Dry Processing.

CALENDAR OF EVENTS

First announcement and call for papers

February, 2009

Two-page abstract deadline

May 31, 2009

Notification of acceptance

July 10, 2009

Early Registration

July, 2009

Final announcement/Program

July 25, 2009

Deadline for the special issue of JJAP

September 23, 2009

Secretariat

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The Japan Society of Applied Physics
The Korean Institute of Surface Engineering
Korean Vacuum Society